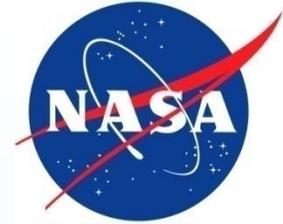


**NEPP Electronic Technology Workshop  
June 22-24, 2010**

National Aeronautics  
and Space Administration



# **Nonvolatile Memory Technology for Space Applications**

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Propulsion Laboratory; 3. MEI, Inc./NASA GSFC;  
4. NASA**

***June 23, 2010***



# Introduction

## Nonvolatile Memories

- **Flash (NAND, NOR)**
- **Charge Trap**
- **Nanocrystal Flash**
- **Magnetic Memory (MRAM)**
- **Phase Change--Chalcogenide, (CRAM)**
- **Ferroelectric (FRAM)**
- **CNT**
- **Resistive RAM**



## Flash Background

### ***–Disadvantages***

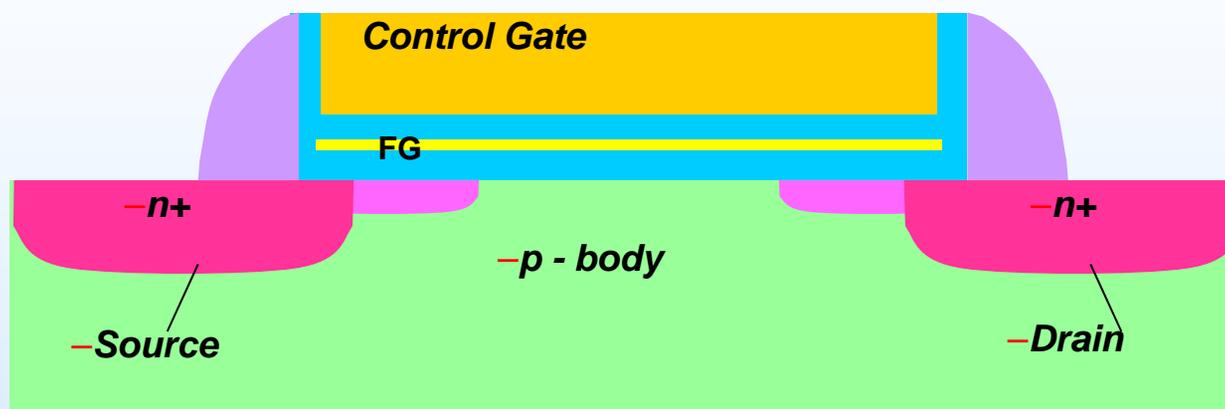
- ***Slow programming***
- ***Wear out***
- ***Scaling/retention***

### ***–Advantages***

- ***Cost per bit***
- ***Low power***

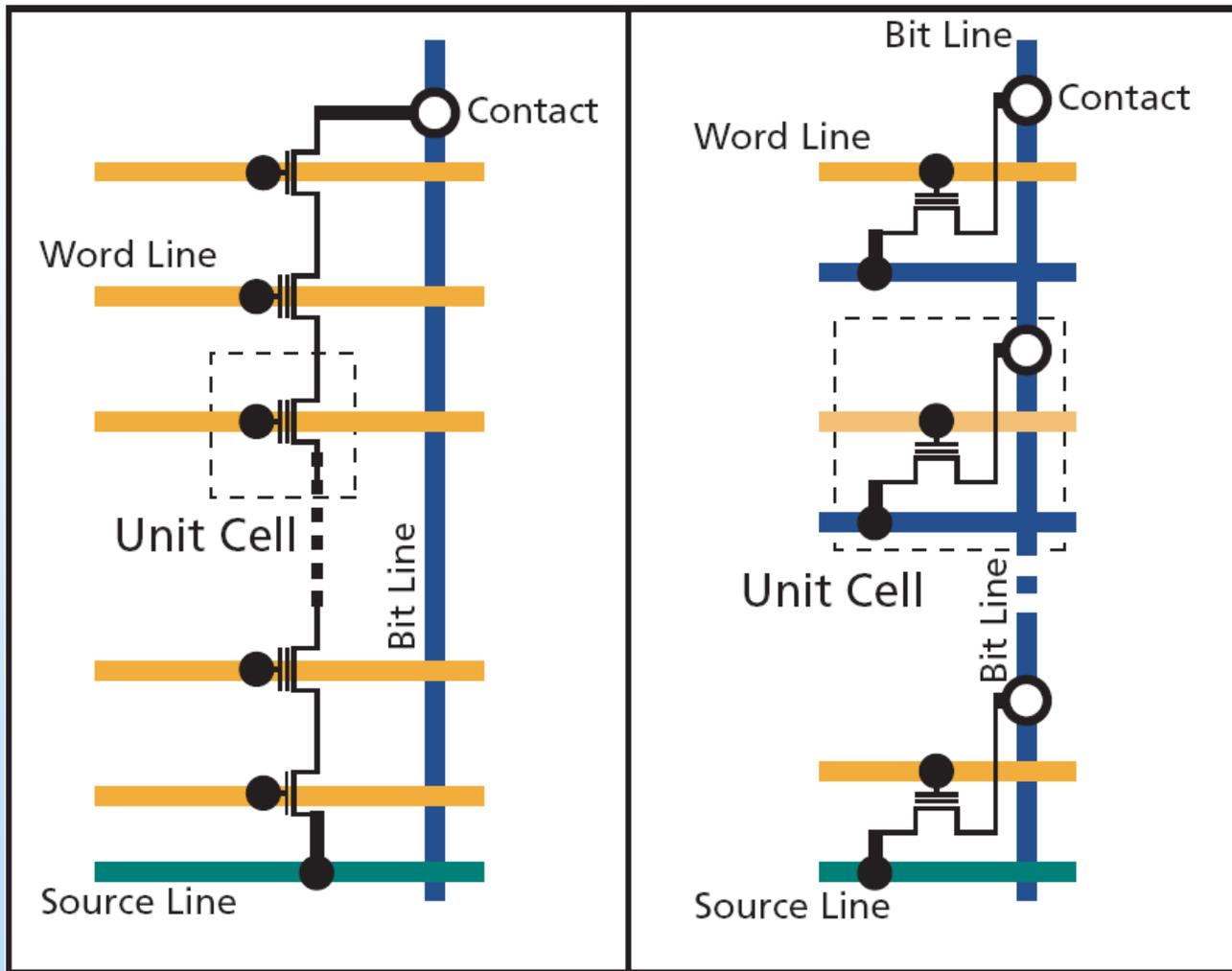
***–Bottom Line: Heavily used in hand-held, battery-powered consumer electronics (cell phones, iPods, digital cameras, MP3)***

# Floating Gate Transistor



- Write (Program) operation—Fowler-Nordheim (FN) injection of electrons into FG
- Erase operation—FN injection of electrons from FG to substrate
- Repeated P/E operations cause damage to tunnel oxide

# Flash Architectures



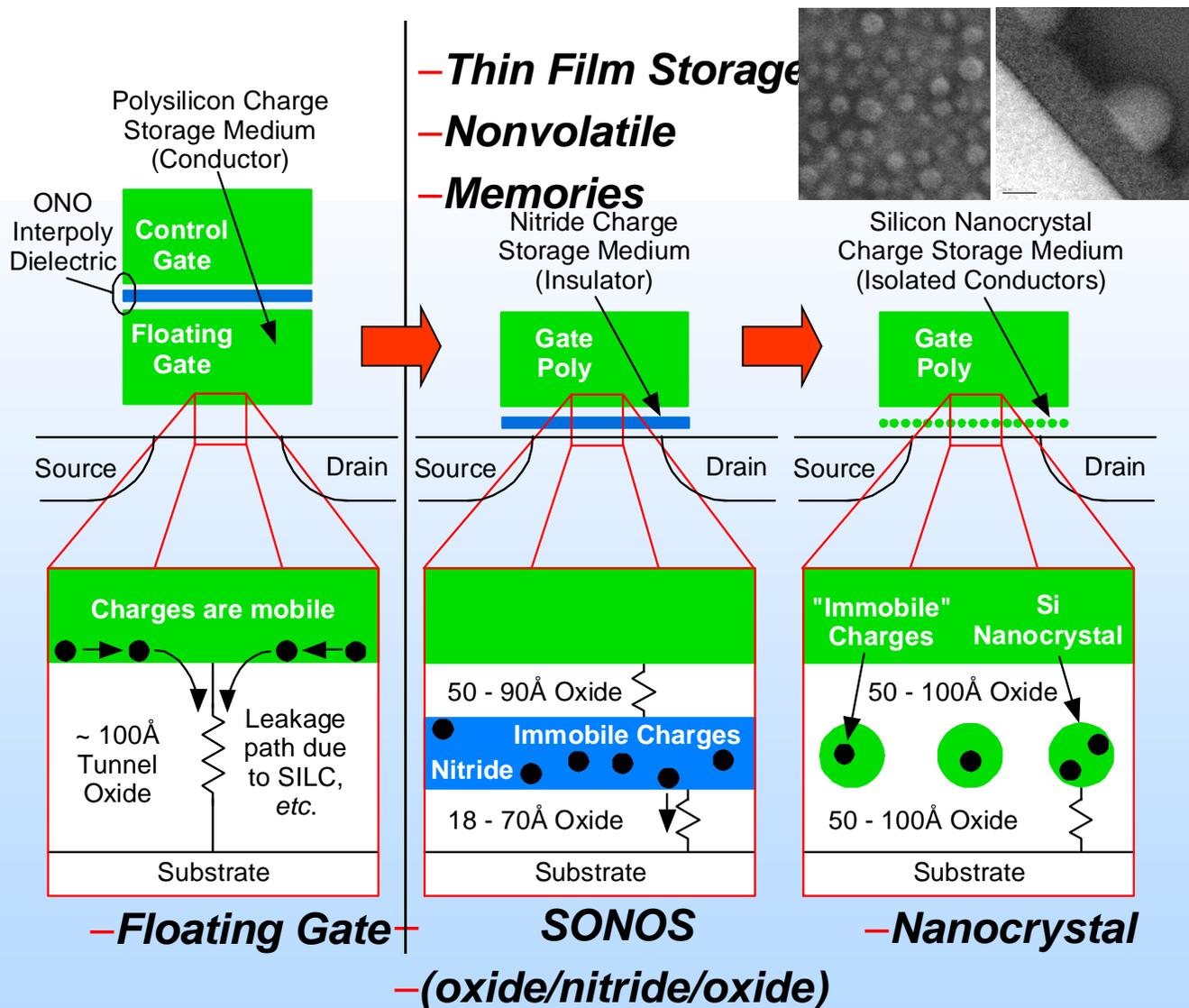
**-NAND**

**-NOR**



# Flash Radiation Response

- **TID response frequently very good for NAND**
- **NOR TID not so good**
- **SEU bit error rate very good compared to most volatile memories**
- **Control logic errors (SEFIs) are biggest problem, mitigation strategies very important**





# Evaluation of Non-Volatile Memory

**-Description:** This is a continuation task for evaluating the effects of scaling (<100nm), new materials, etc. on state-of-the-art (SOTA) non-volatile memory (NVM) technologies. The intent is to:

- Determine inherent radiation tolerance and sensitivities,
  - Identify challenges for future radiation hardening efforts,
  - Investigate new failure modes and effects, and
  - Provide data to technology modeling programs.
- Testing includes total dose, single event (proton, laser, heavy ion), and proton damage (where appropriate). Test vehicles are expected to be a variety of non-volatile memory devices as available including Flash (NAND and NOR), magnetic, phase change, etc...
- Angular effects as well as statistical analysis are key considerations.

## FY10 Plans:

- Probable test structures
- Flash (NAND)
  - Samsung 8G, (SLC and MLC), Micron (8G), Numonyx (4G)
  - Micron 128G stack, Micron 64G monolithic
- Flash (NOR)--Spansion 1G MirrorBit
- Phase change --Numonyx
- FRAM--TI hardened and unhardened
- MRAM—Avalanche Spin Torque
- New tests:
  - Reliability study, retention after radiation exposure and cycling
- Test Guideline
  - Develop draft guideline for radiation testing

## Schedule:

NVM Radiation T&E	2009			2010								
	O	N	D	J	F	M	A	M	J	J	A	S
Monitor MRAM, CRAM, CNT, and FeRAM progress	[Blue shaded cell]											
Micron 128G Stack-SEE				◆								
Numonyx 4G NAND TID, SEE								◆		◆		
Sams, Micron 8G SEE								◆			◆	
Sams, Mic Retention Test				◆	◆	◆	◆	◆	◆	◆	◆	◆
Micron TID			◆							◆		
Current Spike Report				◆								
Test Reports				◆		◆		◆	◆			◆
Spin Torque MRAM TID									◆			

PI: GSFC/Oldham: JPL/irom

## Deliverables:

- Test reports and quarterly reports
- Submissions to IEEE NSREC (TNS and REDW) and SEE Symposium.
- Draft test and application guideline.

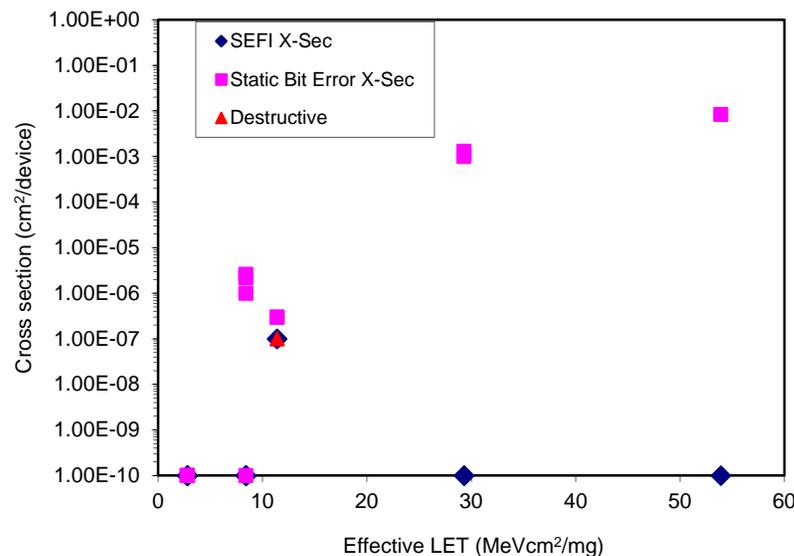
## NASA and Non-NASA Organizations/Procurements:

Beam procurements: TAMU, IUCF, REF  
 NASA Flight Project Funds (Magnetospheric MultiScalar -MMS)  
 Partners: SWRI, Samsung, Micron, Numonyx, Avalanche Semiconductor, Unity

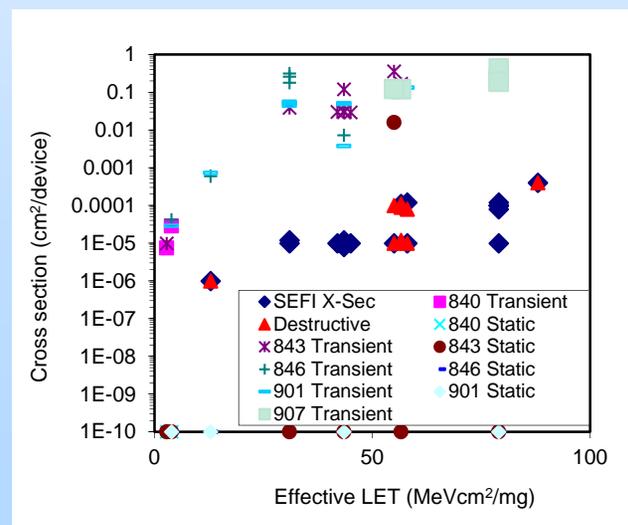


# Evaluation of *Non-Volatile Memory Goals*

- Utilize flash memories as test vehicles for radiation effects understanding of scaled CMOS
- Characterize advanced hardened and unhardened nonvolatile memories. This includes:
  - New materials
  - New technologies and architectures
    - Current flash operate at 3.3V, 40 MHz
    - Increase speed with new 45 nm (16G SLC)
- Identify new failure modes—**including combined effects**
- Develop new test methods and identify mitigating strategies



## New failure modes





## Expected Impact to Community

- **NVM has always been critical in some applications, e.g., critical flight data, and flight control software**
- **Solid state NVM starting to be used in SSR (Solid State Recorders), replacing volatile memories**
- **Solid state NVM has speed advantage over hard disk drives**
- **NAND flash has advantage over most alternatives in cost per bit**

# Nonvolatile Memory Evaluation Status



- **Phase Change**—samples obtained from Numonyx, SEE and TID testing performed
- **STT-MRAM**—Avalanche to supply test structures, TID proton test planned
- **CNT**—LM to supply test structures, unclear when
- **FeRAM**—TI, compare response of hardened and unhardened versions
- **Cypress NVSRAM**—samples received, laser test planned
- **Unity**—transistor-less RAM, to supply test structures



## Non-Volatile Memory Schedule

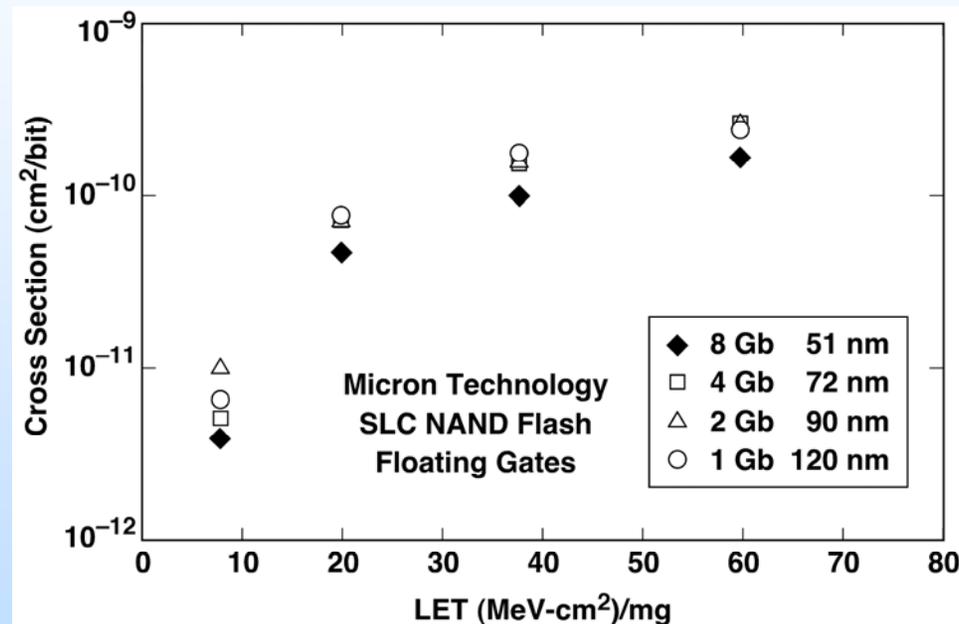
<b>FY10 Deliverables</b>	<b>Quarter Due</b>	<b>Quarter Completed</b>	<b>Notes</b>
<b>Micron 8G, 64G Flash HI Tests</b>	<b>Test 4QFY10 Report 1QFY11</b>		
<b>Micron 32G MLC HI Test</b>	<b>1Q FY10</b>	<b>1Q FY10</b>	<b>NSREC 2010 DW</b>
<b>Numonyx 4GTID/HI tests</b>	<b>TID 4QFY10 HI 3QFY10</b>	<b>HI 3Q FY10</b>	
<b>Spansion 1G MirrorBit NOR TID</b>	<b>Test 4QFY10 Report 4QFY10</b>		<b>Postponed from FY09</b>
<b>Micron 32G MLC TID</b>	<b>2Q FY10</b>	<b>2Q FY10</b>	<b>NSREC 2010 DW</b>
<b>Micron, Samsung Retention Tests</b>	<b>Begin 4QFY10 Continue FY11</b>		<b>NSREC paper to be submitted for July 2011</b>
<b>SP-MRAM TID Test</b>	<b>3QFY10</b>		



## Highlights/Accomplishments

# Single Event Upset Results

- SEU events were measured at BNL on SLC devices (1, 2, 4 & 8Gb).
- All three samples showed excellent agreement.
- No noticeable scaling effect in the range of 120-72 nm
- Error bars smaller than plotting symbols
- There is a reduction in the SEU cross section at 51 nm feature size.



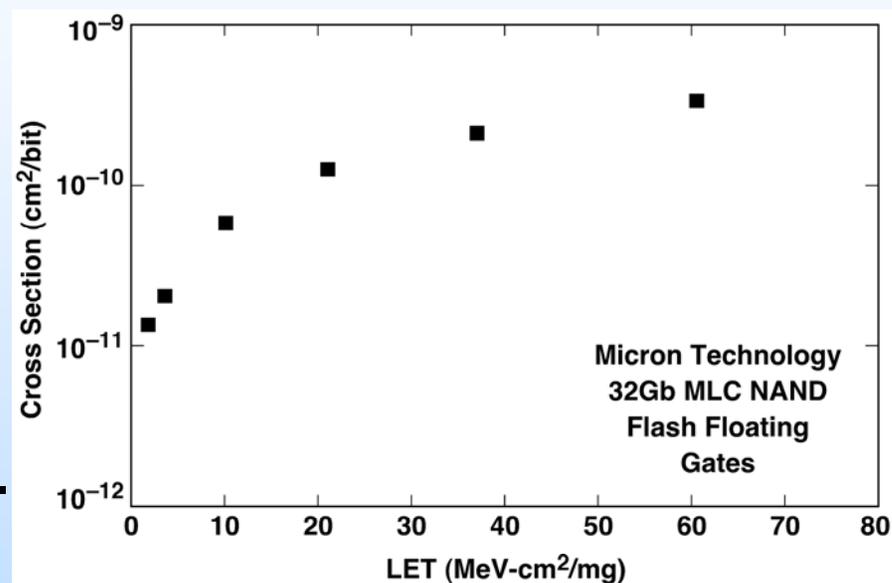
– *Measured SEU cross-sections for Micron Technology SLC NAND flash memories. Only minimal dependence on feature size.*



# Highlights/Accomplishments

## Single Event Upset Results

- The three samples measurements show excellent agreement.
- The FG SEU cross-section per bit is on the order of  $3 \times 10^{-10}$  cm<sup>2</sup>/bit. Error bars smaller than plotting symbols.
- The FG SEU rate is  $5.1 \times 10^{-9}$  per bit per day for the background GCRs environment.
- Micron 32G MLC NAND, 32 nm technology.



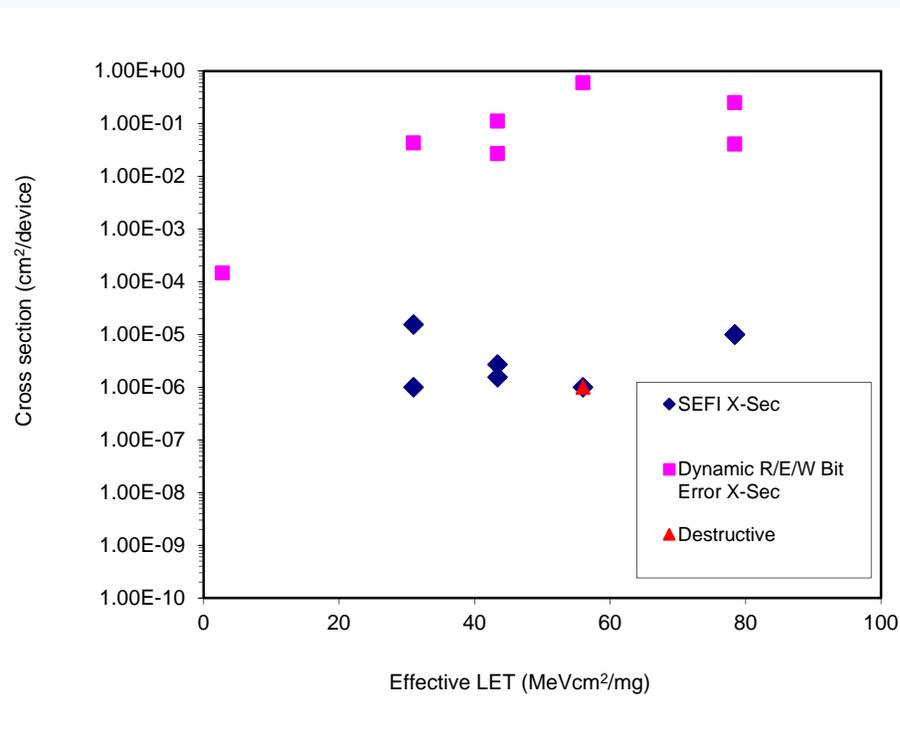
***–SEU cross-section for Micron Technology 32Gb MLC NAND flash memory, order of magnitude smaller than 8G MLC***



# Highlights/Accomplishments

## Numonyx 4G NAND SEE Test Results

- ***One destructive event after  $2.3 \times 10^7$  Xe ions/cm<sup>2</sup>, equivalent to  $2.7 \times 10^9$  years in geosynchronous orbit***
- ***SEU rate manageable, especially with EDAC***
- ***SEFI impact unclear, mitigation required***

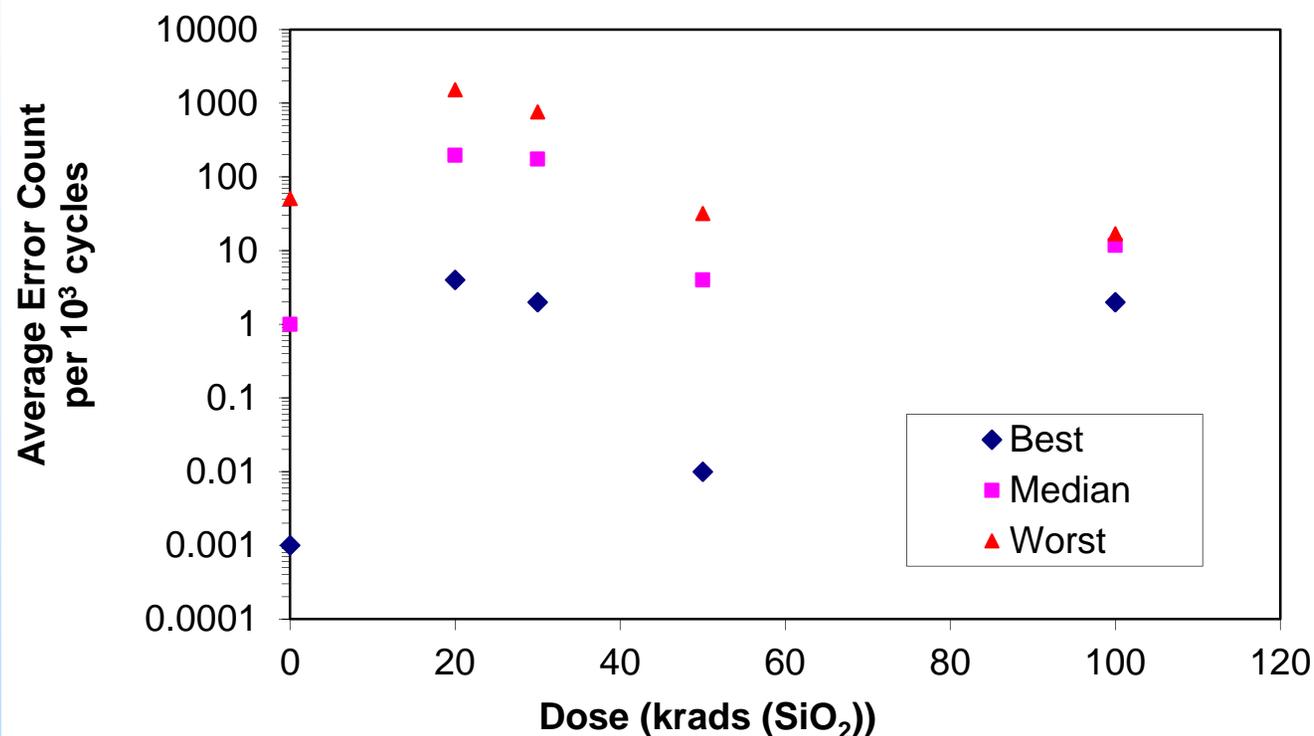


***– Not enough data to endorse for flight programs, yet, but initial results are promising***



# Highlights/Accomplishments

## Reliability/Endurance Study

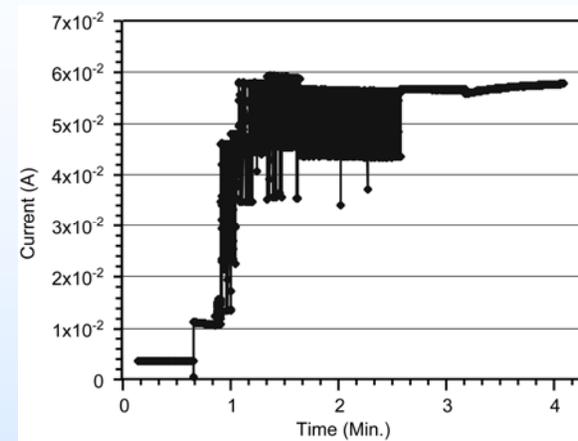
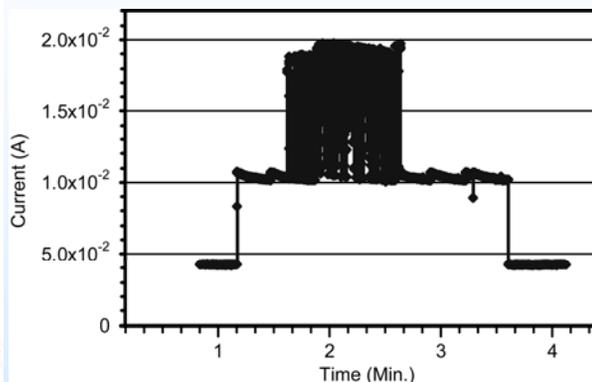
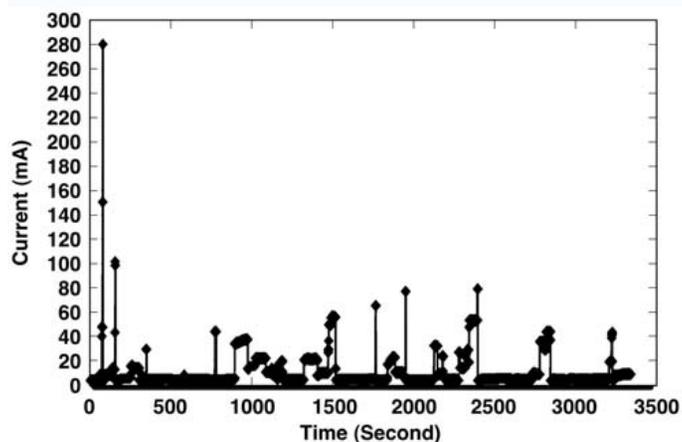


***No clear indication that radiation exposure reduces flash endurance***



# Highlights/Accomplishments

## Current Spikes



- ***Current spikes observed in some experiments, not in others***
- ***Two joint experiments have failed to explain differences***
- ***Agreed to disagree, for now***



## ■ Phase Change Highlights

- Heavy ion testing performed at TAMU
- Chalcogenide storage element appeared to be “bullet proof”
- Unhardened commercial substrate suffered SEL
- TID better than 100 krads ( $\text{SiO}_2$ )



## Plans (FY10/11)

- **Reliability study—retention after cycling and radiation exposure**
- **Characterize Micron single die, SLC 64G NAND (25 nm)**
- **Compare SLC/MLC response (e.g., Samsung 8G)**
- **Prepare draft test guideline document for NVM testing**
- **Monitor development of new NVM technologies, perform testing as test vehicles become available**